

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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C. Healion
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Apple No.	:	10/587,194	Confirmation No. 8444
Applicant	:	Jean-Louis Stehle	
Filed	:	July 24, 2006	
Title	:	PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY IN THE EXTREME UV OR SOFT X-RAY RANGE	
TC/A.U.	:	1795	
Examiner	:	Jonathan G. Jelsma	
Docket No.	:	58059/N75	
Customer No.	:	23363	

AMENDMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Post Office Box 7068
Pasadena, CA 91109-7068
May 28, 2009

Commissioner:

In response to the Office action of November 28, 2009, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.